

Supplementary Materials

Hot Electron Driven Photocatalysis using Sub-5 nm Gap Plasmonic Nanofinger Arrays

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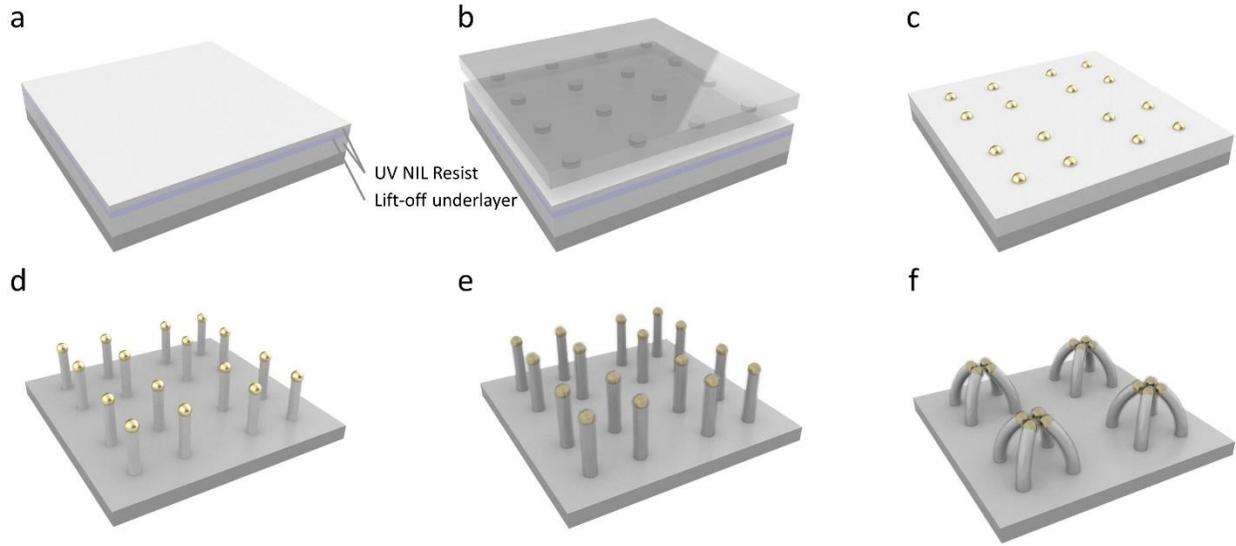


Figure S1. Fabrication procedure of collapsible nanofingers. a) Spin-coat 600 nm UV NIL resist, 100nm lift-off layer and 100nm UV NIL resist on the substrate. b) Perform UV curable nanoimprint and then etch residual layer and lift-off layer. c) Deposit 50 nm Au followed by lift-off process to form Au nanoparticle array onto the thick UV imprint resist layer. d) Perform RIE to obtain nanofinger array. e) Deposit 2 nm TiO_2 thin film on the nanofinger array using ALD. f) Soak fabricated sample into ethanol solution and then air-dry at room temperature to get collapsed nanofinger array.